

In the Abstract

Please substitute the following amended Abstract for the Abstract as currently pending (deleted matter is shown by strikethrough and added matter is shown by underlining):

A method and apparatus for providing a pattern on a solid dosage form, in which powder material is applied in a pattern to a substrate ~~[(3)]~~. A mask ~~[(5)]~~ having an aperture is provided between a source ~~[(1)]~~ of the powder material and the substrate ~~[(3)]~~ and the powder material is applied to the substrate through the mask ~~[(5)]~~. Relative movement of the substrate with respect to the source ~~[(1)]~~ of powder material is effected during the pattern application process.